B3

such as elimination of metallic contaminants by HCl, thus, transporting effect of atomic hydrogen is not mentioned there at all.--

On page 14 before the last full paragraph insert the following:

B4

--In a specific embodiment, a flow rate of molecule of hydrogen-chloride or hydrogen-bromide, which is used as Gas-B in total Gas-C flow is defined as the ratio of an amount of hydrogen atom in Gas-B to that in Gas-A is larger than 1/480.--

IN THE CLAIMS:

Please cancel claims 6 and 22, amend claims 1-3, 5, and 21. Note that claims remain unchanged, but are reproduced in the "Version with markings to show changes made" for the Examiner's convenience and reference.

IN THE CLAIMS

B5

1. (Twice Amended) A method of surface treatment in a substantially downstream position of a plasma source to substantially prevent an undesirable influence of a reactive species from the plasma source, where an object to be processed is downstream from the plasma source, the method comprising generating a plasma discharge including a gas-C, the gas-C comprising a Gas-A molecule containing essentially hydrogen as an element and a Gas-B containing essentially a halogen and/or a halide; wherein said plasma discharge is substantially free from an oxygen bearing species; and wherein the Gas B is selected from chlorine, hydrogen chloride, bromine, or hydrogen bromide; wherein Gas C comprises a flow rate defined as a ratio of an amount of hydrogen atom in Gas-B to that in Gas-A is larger than 1/480.

2. (Twice Amended) The method of claim 1 further comprising injecting a Gas-D in the downstream of the plasma of Gas-C to treat the object comprising a surface in a downstream position of the Gas-D injection.

3. (Twice Amended) The method of claim 1, wherein using the gas B is selected from chlorine, bromine and/or iodine.

5. (Previously Amended) The method of claim 3, wherein Gas-B does not contain an oxygen atom.